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Substitu	te for form 1449/PTO			Application Number	10/634,220	
INF	ORMATION	DIS	CLOSURE	Filing Date	August 5, 2003	
STA	TEMENT E	SY A	PPLICANT	First Named Inventor	Kryliouk et al.	
				Art Unit		
(Use as many sheets as necessary)				Examiner Name		
Sheet	1	of	1	Attorney Docket Number	5853-413	

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7		NIKISHIN et al., "High quality GaN grown on Si(111) by gas source molecular beam epitaxy with ammonia," Applied Physics Letters, 75:2073-2075, 1999	
R		ZHANG et al., "Enhanced optical emission from GaN films grown on a silicon substrate," Applied Physics Letters, 74:1984-1986, 1999	
7	/	LINTHICUM et al., "PROCESS ROUTES FOR LOW DEFECT-DENSITY GAN ON VARIOUS SUBSTRATES EMPLOYING PENDEO-EPITAXIAL GROWTH TECHNIQUES," MRS Internet J. Nitride Semicond. Res. 4S1, G4.9, 1999	
2		STRITTMATTER et al., "Low-pressure metal organic chemical vapor deposition of GaN on silicon(111) substrates using an AlAs nucleation layer," Applied Physics Letters, 74:1242-1244, 1999	
R		SANCHEZ-GARCIA et al., "Ultraviolet electroluminescence in GaN/AlGaN single-heterojunction light-emitting diodes grown on Si(111)," Journal of Applied Physics, 87:1569-1571, 2000	
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Examiner	1	Date 0/18/0	: i

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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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7	_	KRYLIOUK et al., "SINGLE CRYSTAL GAN SUBSTRATE GROWN by HYDRIDE-METAL ORGANIC VAPOR PHASE EPITAXY (H-MOVPE)," Electromechanical Society Proceedings, 98-18:99-107, 1998.	
N		LUKAS et al., "OPTIMIZATION OF PHASE DIAGRAMS BY A LEAST SQUARES METHOD USING SIMULTANEOUSLY DIFFERENT TYPES OF DATA," CALPHAD, 1:225-236, 1977.	
R	-	SUNDMAN et al., "THE THERMO-CALC DATABANK SYSTEM," CALPHAD, 9:153-190, 1985.	

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